



Form 1449 (Modified)

**Information Disclosure
Statement By Applicant**

(Use Several Sheets if Necessary)

Atty Docket No.
LAM1P177/P1139

Applicant:
KANG et al.

Filing Date
August 26, 2003

Application No.:
10/648,953

Group
2811

U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A1.						
	A2.						
	A3.						
	A4.						
	A5.						
	A6.						
	A7.						
	A8.						
	A9.						
	A10.						

Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
	B1.							
	B2.							
	B3.							
	B4.							
	B5.							

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	C1.	U.S. Application No. 11/016,455, entitled "Reduction of Etch Mask Feature Critical Dimensions", by inventors Huang et al., filed 12/16/04.
	C2.	U.S. Application No. 11/208,098, entitled "Etch Features with Reduced Line Edge Roughness", by inventors Sadjadi et al., filed 08/18/05.
	C3.	
	C4.	

Examiner	Date Considered
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Examiner. Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.